

ABSTRACT OF THE DISCLOSURE

An apparatus for measuring feature widths on masks **1** for the semiconductor industry is disclosed. The apparatus encompasses a carrier plate **16** that is retained in vibrationally decoupled fashion in a base frame **14**; a scanning stage **18**, arranged on the carrier
5 plate **16**, that carries a mask **1** to be measured, the mask **1** defining a surface **4**; and an objective **2** arranged opposite the mask **1**. A liquid **25** is provided between the objective **2** and the surface **4** of the mask **1**.